L Number	Hits	Search Text	DB	Time stamp
1	2	"20020086556"	USPAT;	2003/08/04 13:30
	_		US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
3	3477	((silicon adj monoxide) or SiO) near12 (source target	USPAT;	2003/08/04 15:12
		evaporat\$3)	US-PGPUB;	
	1		EPO; JPO;	
			DERWENT;	
	100		IBM_TDB	
4	182	(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire	USPAT;	2003/08/04 14:49
		or (aluminum adj oxide)) near12 (source target evaporat\$3))	US-PGPUB;	-
) and (((silicon adj monoxide) or SiO) near12 (source target evaporat\$3))	EPO; JPO; DERWENT;	
		evaporation)	IBM_TDB	
5	3634	((silicon adj monoxide) or SiO) near15 (sputter\$4 evaporat\$3	USPAT;	2003/08/04 14:49
	3004	cosputter\$4 coevaporat\$3)	US-PGPUB;	2003/00/04 14.43
		oospattera cocvaporatao)	EPO; JPO;	
			DERWENT;	
ļ			IBM_TDB	
6	5448	((silicon adj monoxide) or SiO) near15 (source target	USPAT;	2003/08/04 14:50
		sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
7	16331	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire	USPAT;	2003/08/04 15:12
		or (aluminum adj oxide)) near12 (source target evaporat\$3	US-PGPUB;	
		coevaporat\$3 sputter\$4 cosputter\$4))	EPO; JPO;	
1			DERWENT;	
8	201	(((silicon adj monoxide) or SiO) near15 (source target	IBM_TDB USPAT;	2003/08/04 14:53
0	201	sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) same	US-PGPUB;	2003/06/04 14.55
		(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire	EPO; JPO;	
		or (aluminum adj oxide)) near12 (source target evaporat\$3	DERWENT;	
		coevaporat\$3 sputter\$4 cosputter\$4)))	IBM_TDB	
9	16	((((silicon adj monoxide) or SiO) near15 (source target	USPAT;	2003/08/04 14:58
		sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) same	US-PGPUB;	
		(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire	EPO; JPO;	
		or (aluminum adj oxide)) near12 (source target evaporat\$3	DERWENT;	
	ļ	coevaporat\$3 sputter\$4 cosputter\$4)))) and (gate adj	IBM_TDB	
		(isolat\$3 insulat\$3 dielectric oxide dioxide))		
10	21	(((silicon adj monoxide) or SiO) near15 (source target	USPAT;	2003/08/04 15:13
		sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) and	US-PGPUB;	
		(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near12 (source target evaporat\$3	EPO; JPO; DERWENT;	
		coevaporat\$3 sputter\$4 cosputter\$4))) and (gate adj	IBM_TDB	
		(isolat\$3 insulat\$3 dielectric oxide dioxide))	10101_100	
11	5	((((silicon adj monoxide) or SiO) near15 (source target	USPAT;	2003/08/04 15:01
		sputter\$4 evaporat\$3 cosputter\$4 coevaporat\$3)) and	US-PGPUB;	2000,00,0110.01
'		(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire	EPO; JPO;	
		or (aluminum adj oxide)) near12 (source target evaporat\$3	DERWENT:	
		coevaporat\$3 sputter\$4 cosputter\$4))) and (gate adj	IBM_TDB	
		(isolat\$3 insulat\$3 dielectric oxide dioxide))) not (((((silicon	_	
		adj monoxide) or SiO) near15 (source target sputter\$4		
		evaporat\$3 cosputter\$4 coevaporat\$3)) same (((("Al.sub.2"		
		adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum		
		adj oxide)) near12 (source target evaporat\$3 coevaporat\$3		
		sputter\$4 cosputter\$4)))) and (gate adj (isolat\$3 insulat\$3		
10		dielectric oxide dioxide)))	LICDAT	0000/00/04 45 04
12	354	204/298.26.ccls.	USPAT;	2003/08/04 15:01
			US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
	1		.5	1

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			- · · · · · · · · · · · · · · · · · · ·	000010010
13	5	((silicon adj monoxide) or SiO) and 204/298.26.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/08/04 15:11
14	60466	(("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/08/04 15:52
15	317	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:52
16	213	(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))) and @ad<20010104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM TDB	2003/08/04 15:14
17	83	(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))) and @rlad<20010104	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:14
18	230	((((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))) and @ad<20010104) (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 (Si or silicon)) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))) and @rlad<20010104)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:14
19	1461	(("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:52
21	54	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) same (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:53
20	11	((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:53
22	43	(((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) same (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide))) not (((("Al.sub.2" adj "O.sub.3") or Al2O3 or alumina or sapphire or (aluminum adj oxide)) near15 ((Si or silicon) near8 (dop\$3))) near20 (gate adj (isolat\$3 insulat\$3 dielectric oxide dioxide)))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/08/04 15:56